5th RD50 Workshop on Radiation hard semiconductor devices for very high luminosity colliders CERN, 5-7 May, 2004

Oxygen dimer enriched silicon

- RD50 dimer task force -

Veronique Boisvert, Michael Moll CERN - Geneva - Switzerland

Lennart Lindstrom

Lund University, Sweden Leonid Murin

National Academy of Sciences of Belarus

Iona Pintilie

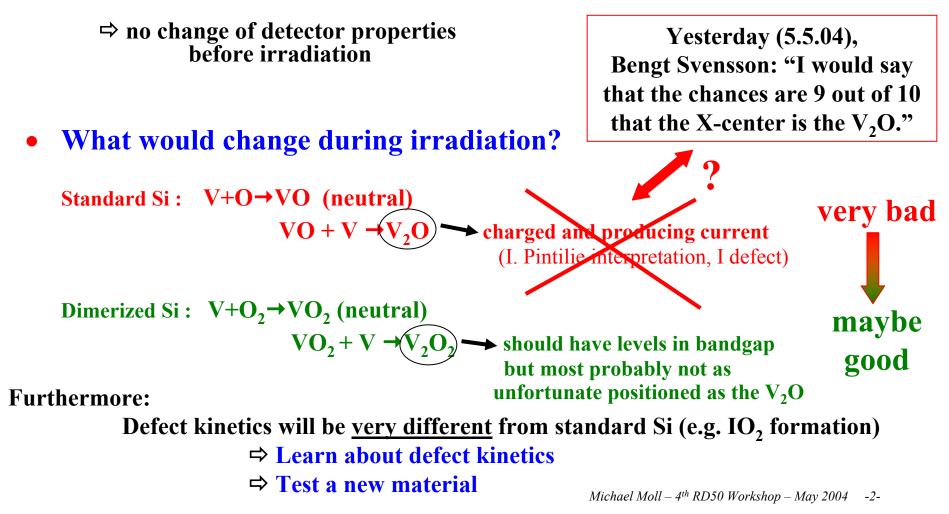
NIMP, Bucharest, Romania

Eckhart Fretwurst, Joerg Stahl Hamburg University, Germany

RD50 Motivation: Defect engineering



- Aim: Produce silicon that contains only O₂ and no mono-atomic O
 - Standard silicon: O (neutral) -- contains oxygen in mono-atomic form (O)
 - **Dimerized silicon:** O₂(neutral) -- contains oxygen in form of dimers (O₂)



RD50 How to create dimers ?



- "Pre-irradiation" of <u>detectors</u> at high temperature
 - Produce point defects at a temperature at which
 - the VO is mobile but does not break up
 - the O₂ is produced but does not break up
 - the formation of thermal donors is kept at a minimum
 - → Co⁶⁰-γ or electron irradiation at 350°C

$$V+O \rightarrow VO$$

 $VO+O \rightarrow VO_2$
 $VO_2 + I \rightarrow O_2$

• Problem:

Formation of many other defects! (e.g. TD) (very strong temperature dependence)

RD50 RD50 dimerization experiments



• First experiment: June 2003

- 6 MeV electrons (KTH Stockholm)
- Fluence of 1x10¹⁸ e/cm²
- Temperature: 330-340 °C
- Samples with different oxygen concentration:
 - Bulk material for FTIR: FZ and CZ (3mm thick from ITME, Poland)
 - **PAD-diodes: FZ, DOFZ, CZ** (0.25cm², p⁺nn⁺, 300µm from Hamburg University)
- Irradiation experiment: CERN PS 24 GeV/c protons up to 10¹⁶ p/cm²

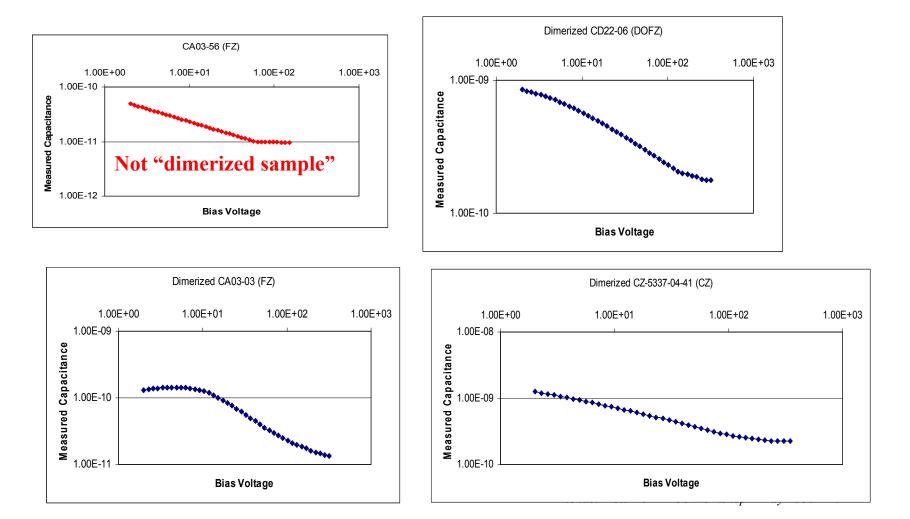
• Second experiment: March/April 2004

- 6 MeV electrons (KTH Stockholm)
- Fluence of 2, 5, 10x10¹⁷ e/cm²
- Temperature: 350°C
- Samples:
 - Bulk material for FTIR: p, n-type MCZ, CZ (Okmetic, ITME)
 - PAD-diodes: CZ, MCZ (Hamburg University, Helsinki Institute of Physics)
- Analysis in progress....

RD50 Diodes after dimerization process



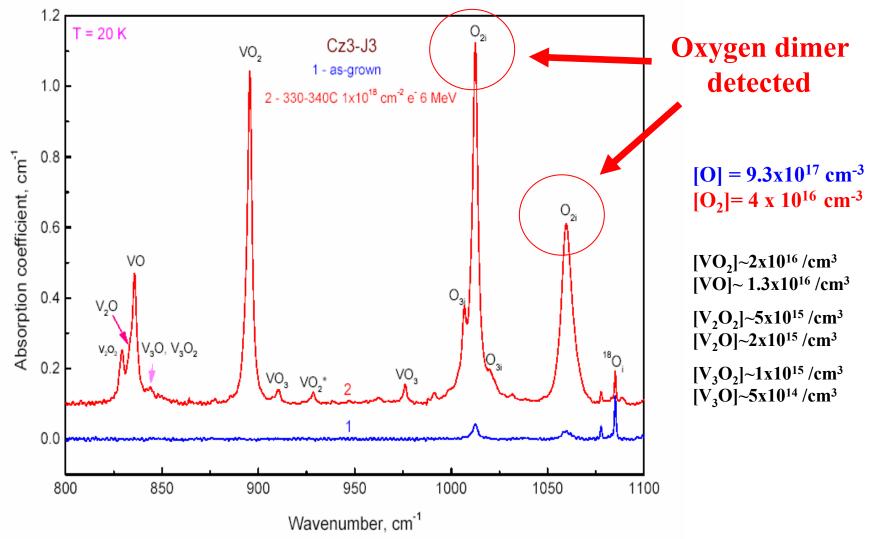
- CV/IV characterization of dimerized diodes
 - All dimerized samples could not be fully depleted



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FTIR results: Cz silicon





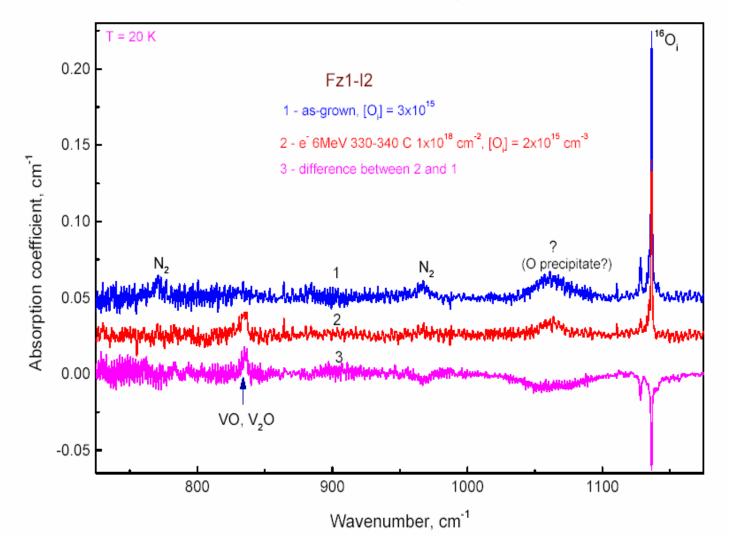
Data: Leonid Murin, Lund & National Academy of Sciences of Belarus



FTIR results: FZ silicon



Data: Leonid Murin, National Academy of Sciences of Belarus

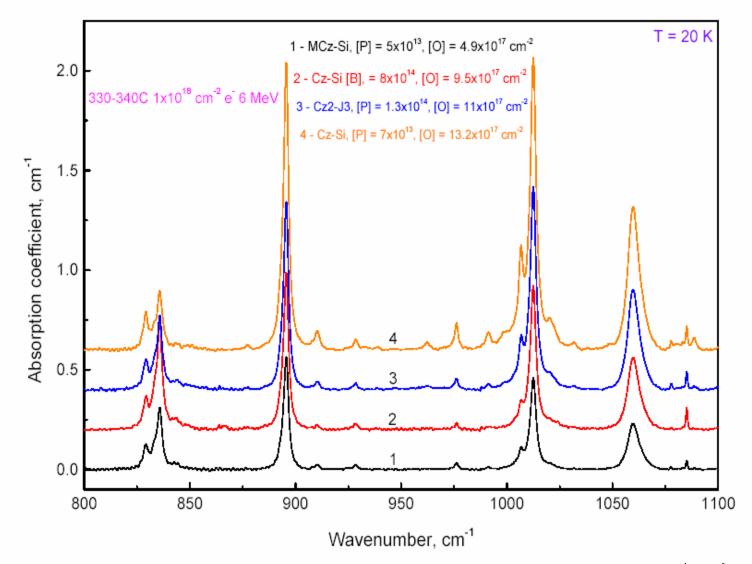




FTIR results – various CZ

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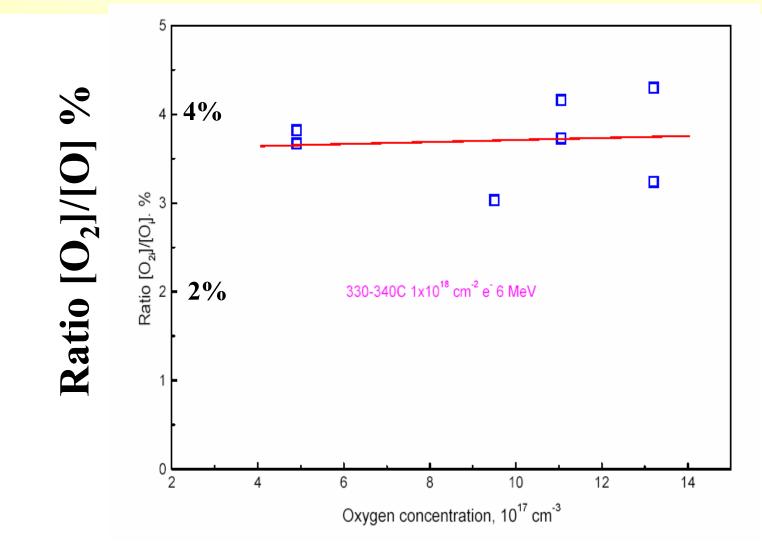
Data: Leonid Murin, Lund & Minsk University





FTIR results- [O] dependence

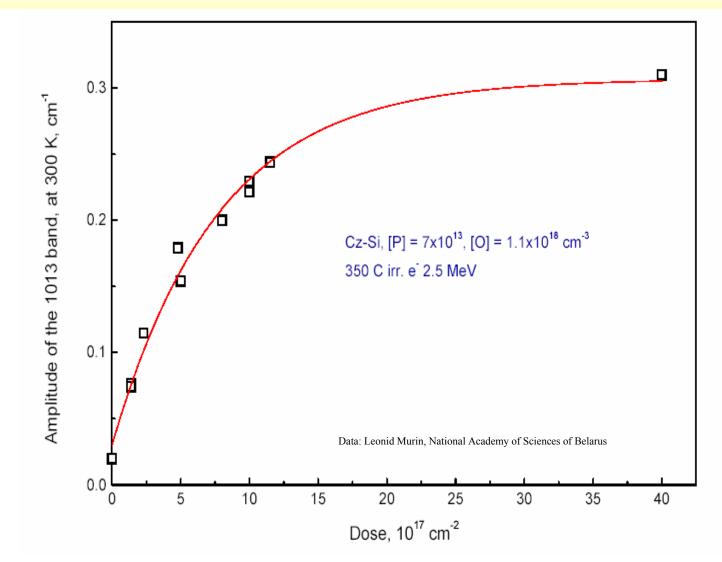




• Only ~4% of the oxygen (O_i) is transformed into oxygen dimers (O_{2i})

RD50 Dimer formation - Saturation





• Increasing the electron fluence leads to saturation of oxygen dimer concentration

RD50 Irradiation test of "dimerized" Si



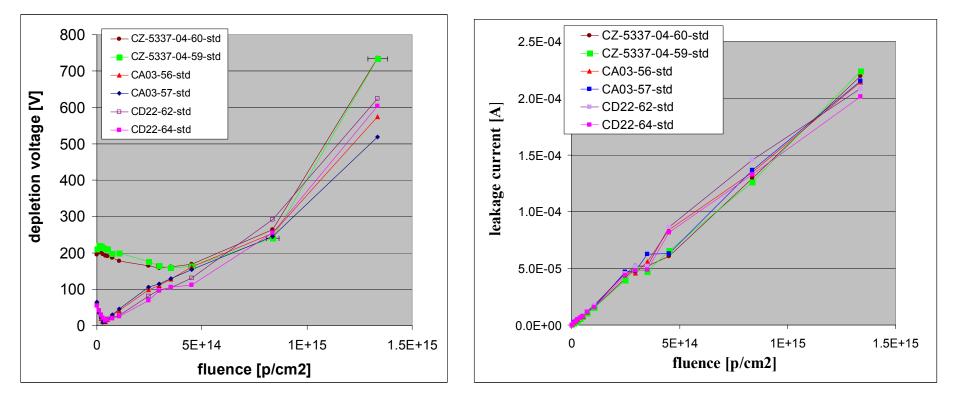
- Performed "CERN scenario" using 24 GeV/c
 - Irradiation up to $1.5 \times 10^{15} \text{ p/cm}^2$
 - Irradiated 9 diodes (Hamburg group, CIS):
 - 3 dimerized diodes: (FZ, DOFZ, CZ)
 - 6 control diodes: (2 FZ, 2 DOFZ, 2 CZ)
- Various bulk samples for IR measurements
 - Irradiated up to 10¹⁶ p/cm²

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24 GeV/c proton irradiation



• Irradiation in "CERN scenario" using 24 GeV/c protons



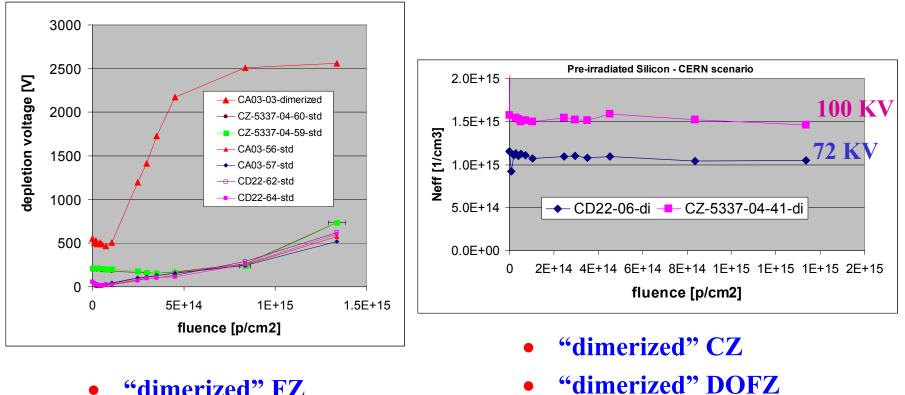
• Expected behavior of control samples





Diodes could not be depleted

- \Rightarrow Infer N_{eff} and V_{dep} using the slope of 1/C² vs V
- \Rightarrow <u>Very unreliable method</u> for irradiated detectors, but best we could do

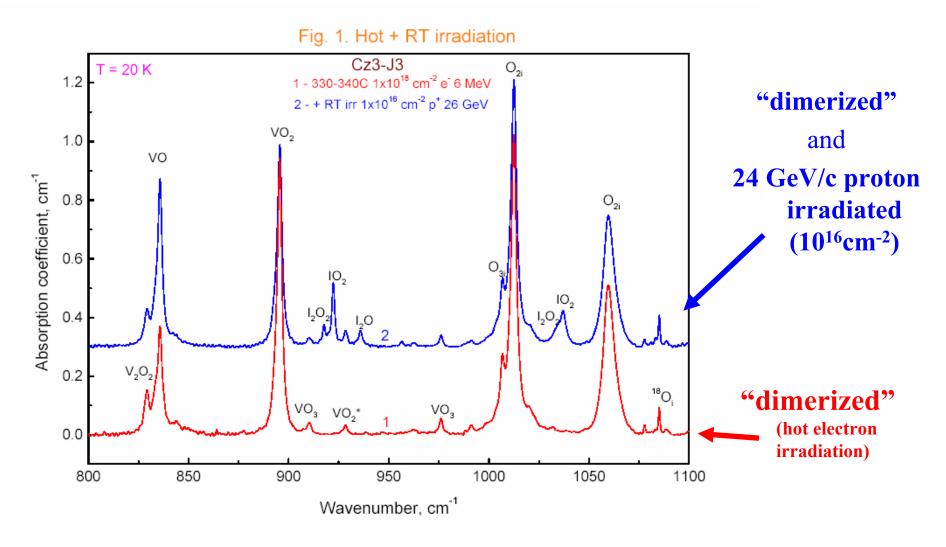


"dimerized" FZ

RD50 Irradiation of dimerized Si (FTIR)

1954-2004 CERN

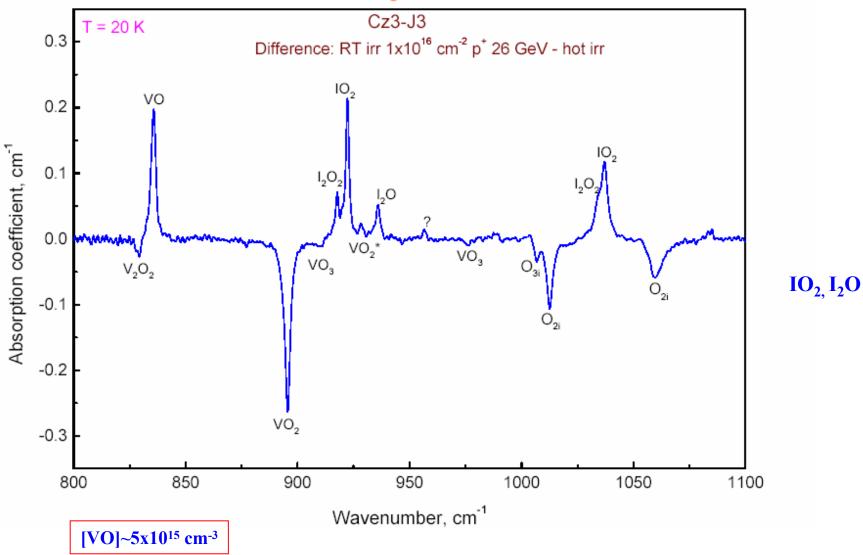
Data: Leonid Murin, National Academy of Sciences of Belarus



RD50 Irradiation of dimerized Si (FTIR)



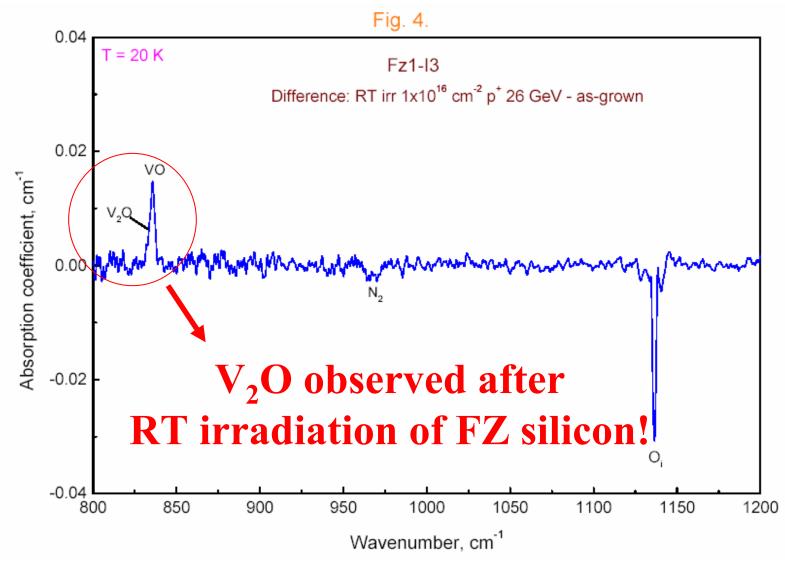
Fig. 2



Data: Leonid Murin, National Academy of Sciences of Belarus

RD50 V₂O in proton irradiated FZ silicon



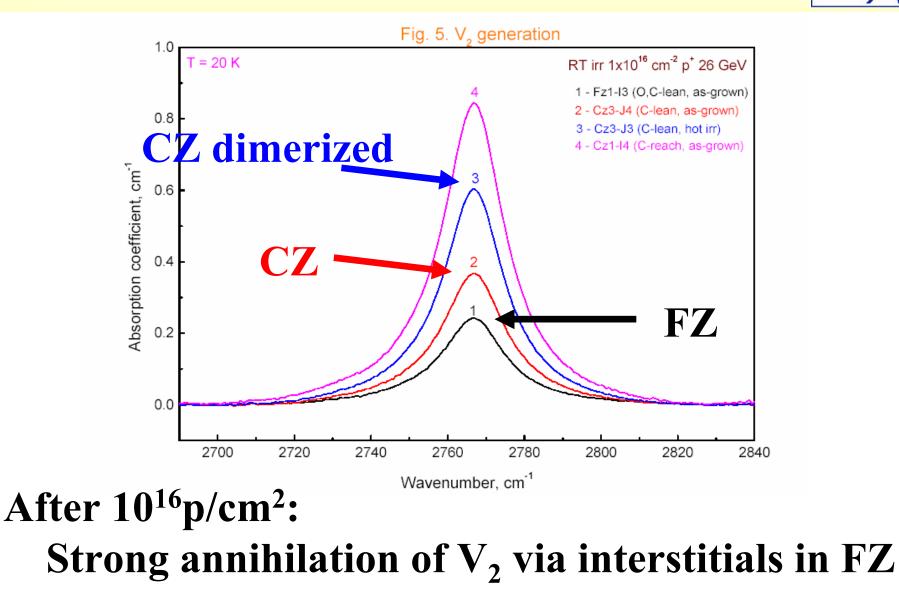


Data: Leonid Murin, National Academy of Sciences of Belarus



V₂ generation after 10¹⁶ p/cm²

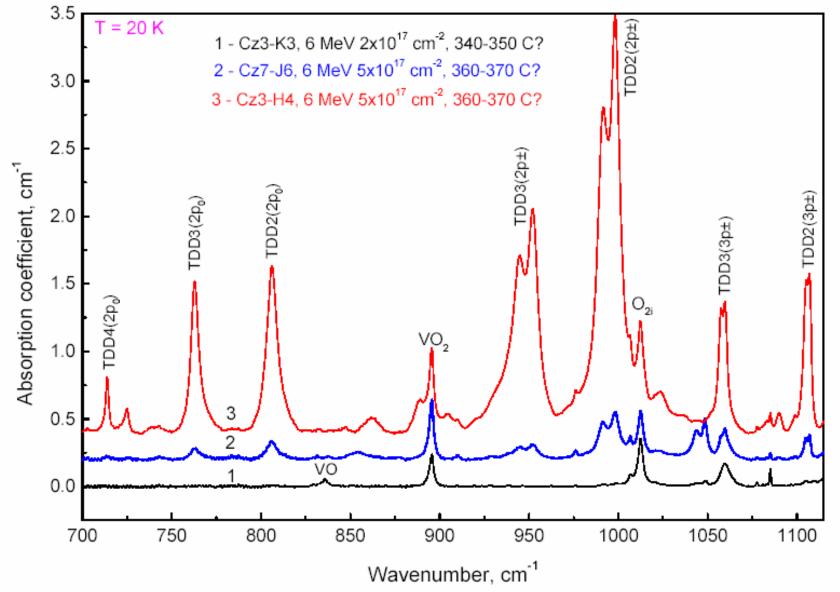




Data: Leonid Murin



Thermal Donor Generation



Data: Leonid Murin

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Michael Moll – 4th RD50 Workshop – May 2004 – 18-

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Conclusions



• Dimerization process (as done by us) creates too many charged defects in silicon diodes could not be depleted after "dimerization"

... we could go down in the electron pre-irradiation fluence, but then we would even produce less dimerscould use thin detectors?

- It is not possible to create a significant amount of dimers in CZ silicon (not more than 5% of the [O] concentration).
 - Also only a small amount of dimers in DOFZ and FZ after dimerization process below detection limit (~10¹⁵cm⁻³)
- Novel ground for defect studies!
 - Identification and characterization of many defects
 - Tuning of simulations
 - Could potentially lead to a usable material?
 - FTIR A microscopic tool that works after an irradiation with 10¹⁶ cm⁻²!

• RD50 dimer task force

- Formed on RD50 Workshop in October 2002... ... after first promising dimer tests of the Brunel group
- Analyses of latest dimerization experiment currently under way (preliminary result: diodes can not be depleted even after the lowest fluence of 2x10¹⁷ cm⁻²)
- Finalize the work with a publication within the coming 3 months
- Give final conclusion in next status report